

TITLE

SUBSTRATE SUPPORT MECHANISM, SUBSTRATE CLEANING DEVICE AND SUBSTRATE PROCESSING METHOD

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ABSTRACT

The disclosure provides one technique for suppressing wear of a cleaning member and unexpected dust generation. A substrate support mechanism 100 includes a first support part 110 which is swingable and has a contact region that can come into contact with a peripheral
10 edge of one surface of a substrate W in a closed state, a second support part 120 which supports the other surface of the substrate W, and a first support part moving part 140 which swings the first support part 110.

15 FIG. 2